

DATA SHEET NexSilTM 85-40

NexSil™ 85-40 Colloidal Silica

PRODUCT DESCRIPTION

NexSilTM 85-40 is an alkaline dispersion of 40 - 60 nm colloidal silica at a 40% SiO₂ concentration in water. The particles are negatively charged. The product can be used in paper, steel and precision polishing applications where large particle size colloidal silica is required.

NexSil 85-40 is a good choice for sapphire polishing and other specialty wafer polishing applications. NexSil 85-40 provides good balance between removal rate and surface finish. Consult NYACOL® for recommendations on starting conditions.

TYPICAL PROPERTIES

Appearance: Light Milky Sol

 SiO_2 Content, %: 39 – 41 Na₂O Content, %: 0.05 – 0.2

Particle Size, nm: 40 – 60 by TEM

Particle Size, DLS, Z-Average, nm: 70 - 90
Specific Surface Area, m²/g: 45 - 75
pH: 8.8 - 9.8
Viscosity, cPs: <20
Surface Charge: Negative

FOR ADDITIONAL INFORMATION OR TO ORDER MATERIAL

Nyacol Nano Technologies, Inc.

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P.O. Box 349

508-881-2220 Local Area

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